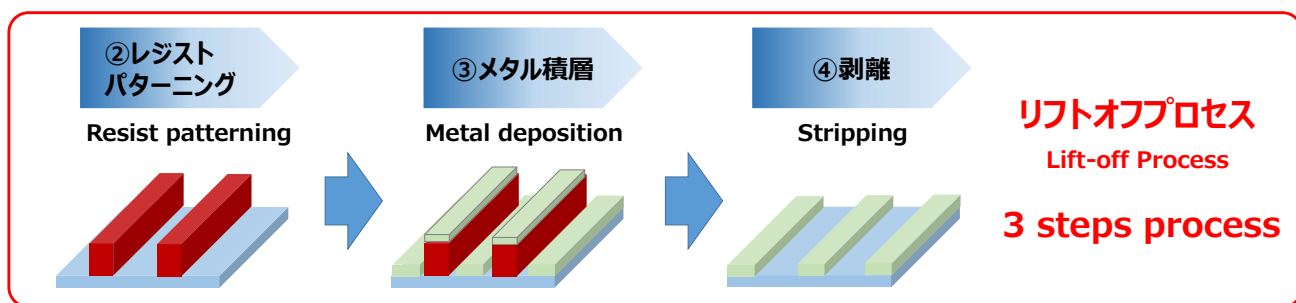
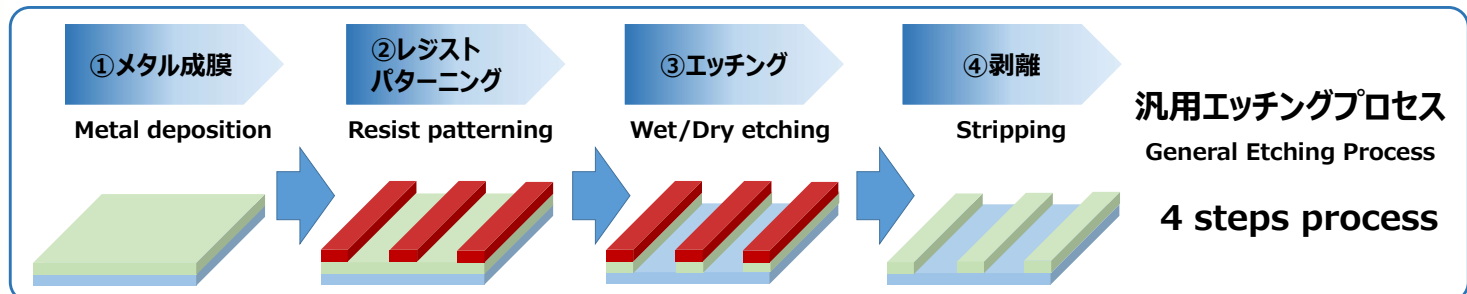


電子部品・半導体デバイス用フォトレジスト

Photoresist for Electronic Components and Semiconductor Devices

リフトオフプロセス

Lift-off Process



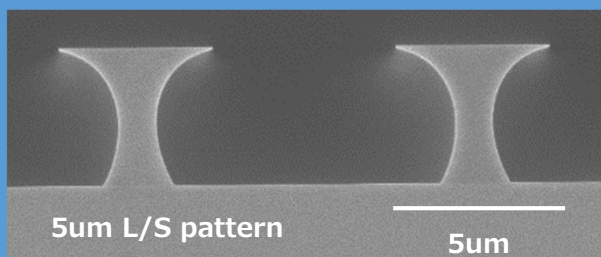
製品ラインナップ

Production Lineup

リフトオフプロセス用単層レジスト

Single layer type of resist for lift-off process

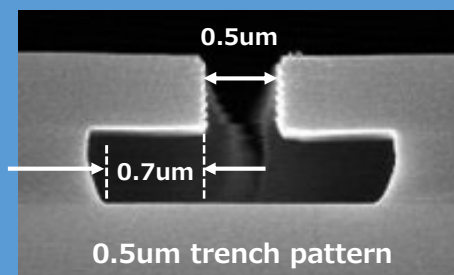
NPR9700 series



リフトオフプロセス用2層レジスト

Double layer type of resist for lift-off process

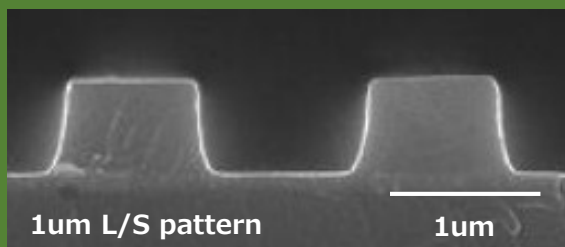
BLX-200 series



フォトマスク製造用レジスト

Photoresist for production of photomask

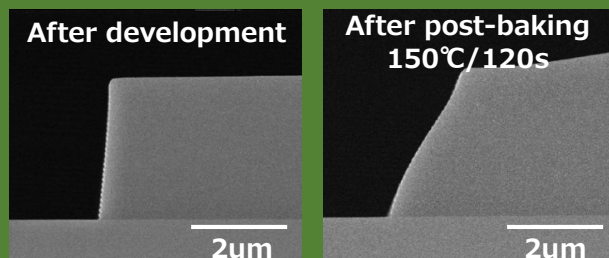
GRX-M200 series



パワーモジュール製造用レジスト

Photoresist for production of power module

PMS-500 series

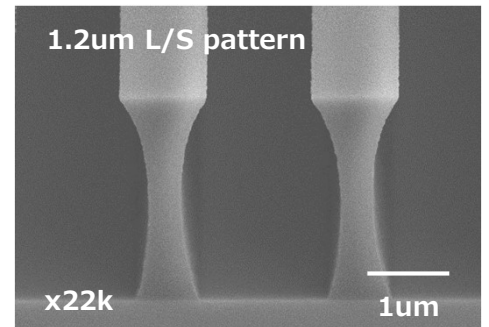
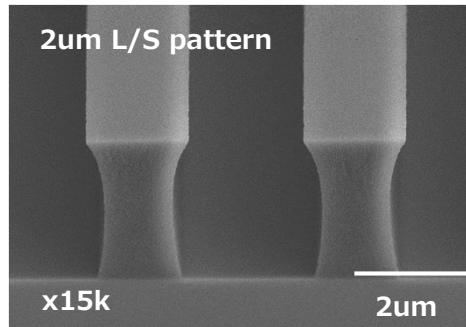
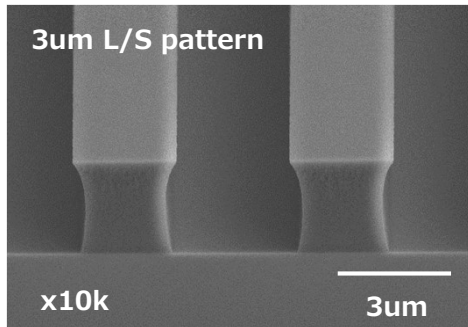


リフトオフプロセス用 単層&2層レジスト

Single/Double Layer Type of Resist for Lift-off Process

リフトオフプロセス用単層レジスト NPR9730

Single layer type of resist for lift-off process



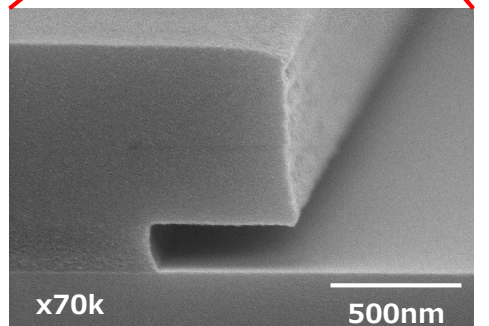
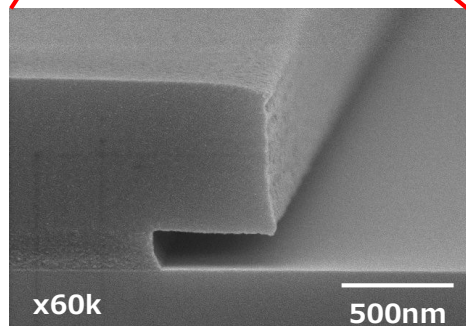
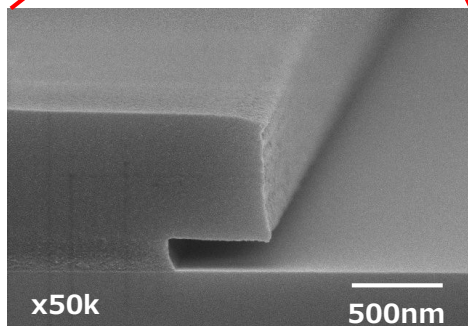
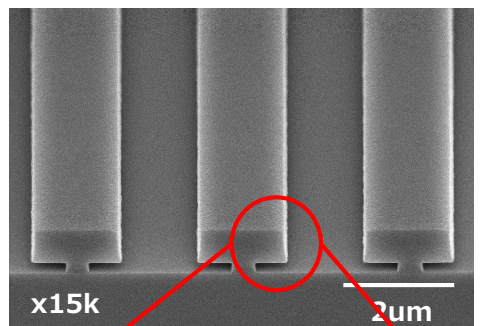
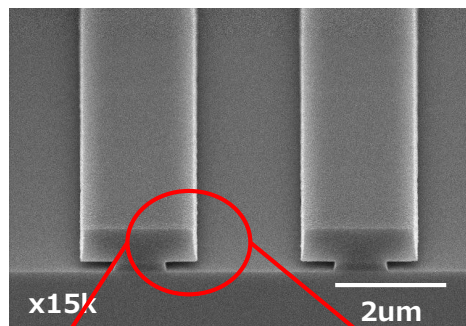
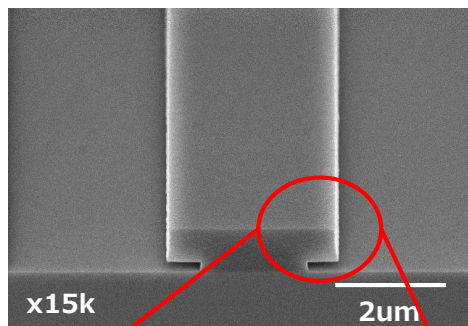
少しラフなメタル分割用途で、短いタクトタイムでの生産用途に適しています。

NPR9730 is suitable for producing the rough divided metal lines.

It's an effective selection for making tact time shorter of your production line to apply our NPR9730.

リフトオフプロセス用2層レジスト BLX-210

Double layer type of resist for lift-off process



タクトタイムは長くなりますが、微細なメタル分割が必要な生産用途に適しています。

The tact time of this process is longer than single layer lift-off process.

Double layer process can make fine divided metal lines without the dry etcher machine.

Please feel free to ask below contact any questions.